

Sheet 1 of 1 FIRST IDS LIST OF REFERENCES CITED BY APPLICANT (FORM PTO-1449) DATED: <u>March 14, 2005</u>				Atty. Docket No. 4856/PCT		Serial No.: To Be Assigned	
				Applicant: Matthias AIKELE et al.			
				U.S. Filing Date: March 14, 2005		Art Unit:	
U. S. PATENT DOCUMENTS							
*EXAMINER INITIAL		DOCUMENT NO.	DATE	NAME	Cl.	Sub- Cl.	Fil. Date
	AA	5,041,898	08/1991	Urabe et al.	-	-	-
	AB	5,747,377	05/1998	Wu	-	-	-
	AC	5,930,595	07/1999	Sridhar et al.	-	-	-
	AD	6,239,473	05/2001	Adams et al.	-	-	-
	AE	6,342,427	01/2002	Choi et al.	-	-	-
FOREIGN PATENT DOCUMENTS							
		DOCUMENT NO.	DATE	COUNTRY	Cl.	Sub- Cl.	Trans. Yes No
OTHER DOCUMENTS							
X	AF	Chunbo Zhang et al.; "Fabrication of thick silicon dioxide layers using DRIE, oxidation and trench refill"; IEEE, 2002, pages 160-163, XP010577620 no month available					
EXAMINER'S SIGNATURE				DATE CONSIDERED			
/Anita Alanko/ (08/02/2010)							
*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.							

ALL REFERENCES CONSIDERED EXCEPT WHERE LINED THROUGH. /A.A./ (08/02/2010)

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